Towards on-chip ultrafast pulse amplification

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Amplification of ultrafast optical signals is key to a large number of applications in photonics. While ultashort pulse amplification is well established in optical gain fibers, it is challenging to achieve in photonic-chip integrated waveguides. Recently, several integrated (quasi-)continuous-wave amplifiers have been demonstrated, based on rare-earth, heterogeneous semiconductor integration or nonlinear parametric gain [1-4]. On-chip amplification of ultrafast pulses, however, remains challenging due to the inherently small mode area and high-optical nonlinearity in integrated waveguides.

Here, we present our recent work towards an on-chip ultrafast amplifier, leveraging large mode-area gain waveguides with tailored group-velocity dispersion (GVD). The amplifier structure combines silicon nitride (Si_3N_4) waveguides with a radio-frequency sputtered thulium-doped alumina gain layer (Tm^{3+} : Al_2O_3), providing large gain bandwidth (1650nm-2000nm) and supporting sub-100 fs pulses. By designing the dimension of the Si_3N_4 waveguide, the waveguide's GVD, the mode confinement, and its overlap with the gain layer is tailored to achieve stable pulse propagation [5], low-loss waveguide bends and large optical gain (Fig. 1a-d) [6,7]. Fig. 1e shows broadband amplification with 10 dB net gain of a pulsed input signal (1820 nm center wavelength, 0.1 mW) in an amplifier characterized by a mode cross-section > 10 μm^2 in the gain section and an estimated Tm^{3+} concentration of $4.0x10^{20}cm^{-3}$. The pump power at 1610 nm is 240 mW. These results, open a pathway towards on-chip amplification of ultrashort pulses, with potential implications for spectroscopy, ranging or nonlinear mid-infrared light generation [8] in a chip-scale integrated photonic setting.



Fig. 1 (a) Amplifier waveguide cross-section (b) Illustration of chip-layout. Black: wide Si_3N_4 waveguide with strong mode confinement. Blue sections: narrow Si_3N_4 waveguide with weak mode confinement and large mode-overlap with the Tm³⁺: Al₂O₃ gain layer. (c) and (d) TE mode profiles of a 1830 nm signal for 1000nm and 300nm-wide Si_3N_4 waveguides, respectively. (e) Optical spectra of the input and output signals.

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References

[1] J. Mu et al., "High-gain waveguide amplifiers in Si3N4 technology via double-layer monolithic integration", Photon. Res. 8, 1634 (2020).
[2] Y. Liu et al., "A photonic integrated circuit–basederbium-doped amplifier", Science 376, 1309–1313 (2022).

[3] Camiel Op de Beeck et al., "Heterogeneous III-V on silicon nitride amplifiers and lasers via microtransfer printing", Optica 7, 386 (2020).
[4] J. Riemensberger et al., "A photonic integrated continuous-travelling-wave parametric amplifier", Nature 612, 56-61 (2022).

[5] J. M. Dudley et al., "Self-similarity in ultrafast nonlinear optics", Nat. Phys. 3, 597 (2007).

[6] N. Singh et al., "Towards CW modelocked laser on chip-a large mode area and NLI for stretched pulse mode locking", Opt. Exp. 28, 15 (2020).

[7] Purnawirman et al., "C- and L-band erbium-doped waveguide lasers with wafer-scale silicon nitride cavities", Opt. Lett. 38, 1760 (2013).
[8] M. Tao et al., "Super-flat supercontinuum generation from a Tm-doped fiber amplifier", Sci. Rep. 6, 23759 (2016).